Mask Order Form

Photomasks Anonymous, Inc., Nowheresville, USA

Company:	U.C. Santa Barbara	Date:	2020-03-26
Name of Requester:	Demis D. John	P.O. Number:	GW**********
Phone Number:	805-893-5934	File Name:	DEMISJAN2020 - Reticle_Layout v1.GDS *(This file contains ONLY the RETICLE_LAYOUT cell, and all polygons moved to a single Layer #1)*
e-mail Address:	demis@ucsb.edu	Grade / Product Name:	**1234-1um** *(corresponds to a "grade" with "minimum feature size = 1.0µm" and Cost etc.)*
Fax Number:			
Deliver Masks to:	Room 1109D		
Address:	Engineering Sciences Bldg. (#225)		
	Nanofabrication Facility		
	Santa Barbara, CA 93106		

Reticle / Mask Requirements

GDSII Level	Title to Appear on Mask	Topcell Structure Name	Chrome Side Down Reading R-Right W-Wrong	Polarity (Digitized/ Drawn Areas to be Clear or Dark)	Reticle/ Mask (Critical Dimension)
1	Demis-CADTutorial-2020	Reticle_Layout	R	Clear	1.0 µm
			(Minimum feature on the CAD file is 0.250µm, so 4 x 0.250µm = 1.0µm)		

Special Instructions:

1. **Data is wafer-scale (1x), intended for 4x reticle for ASML 5500/300 DUV stepper**
2. **Barcode should read "DEM-2020-03" (12 char. max)**